## Large interfacial perpendicular magnetic anisotropy

## in epitaxial Fe<sub>80</sub>Al<sub>20</sub>/MgAl<sub>2</sub>O<sub>4</sub> heterostructures

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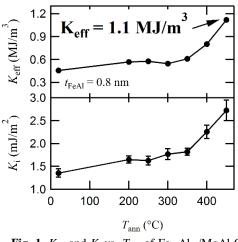
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Large perpendicular magnetic anisotropy (PMA) is a key requirement for magnetic tunnel junction (MTJ) based memory devices. PMA at ferromagnet (FM)/oxide interfaces is generally used to compensate thermal instabilities arising with the downsizing of MTJs. Recently, strong PMA has been reported in Co<sub>2</sub>FeAl/MgAl<sub>2</sub>O<sub>4</sub>(001) heterostructures [1]. Microstructure investigation revealed large PMA in the structure that was attributed to a reduced lattice strain due to the use of MgAl<sub>2</sub>O<sub>4</sub> and the effect of strengthening of the Fe-O hybridization at the interface due to diffusion of Al into the barrier [2]. In this study, we investigated the interfacial PMA using a Fe-Al alloy instead of Co<sub>2</sub>FeAl. We found enhanced effective PMA energy  $K_{eff}$  up to 1.1 MJ/m<sup>3</sup> in Fe<sub>80</sub>Al<sub>20</sub> in contact with an MgAl<sub>2</sub>O<sub>4</sub> barrier.

The following structures were deposited on an MgO(001) single crystal substrate using a magnetron sputtering system with a base pressure of  $4x10^{-7}$  Pa: MgO//Cr (40)/Fe<sub>80</sub>Al<sub>20</sub> ( $t_{FeAl}$ )/Mg (0.2)/Mg<sub>40</sub>Al<sub>60</sub> (0.7)/oxidation /Ru (2) (thickness in nm). The MgO substrate and Cr buffer were annealed at 750°C for 1 h. Fe-Al was deposited by co-sputtering. The barrier (oxide of Mg/MgAl) was formed using an oxygen plasma. Stacks were annealed for 30 min *ex-situ* at temperature  $T_{ann}$ .

In Fig. 1,  $K_{eff}$  for a  $t_{FeA1} = 0.8$  nm film (a) and interface anisotropy  $K_i$  (b) vs.  $T_{ann}$  evaluated by magnetization curves are plotted. At  $T_{ann} = 450^{\circ}$ C, the largest PMA of  $K_{eff} = 1.1$ MJ/m<sup>3</sup> ( $K_{eff}$ · $t_{Fe} = 0.9$  mJ/m<sup>2</sup>) is observed, comparable to electron beam-evaporated Fe/MgO heterostructures [3].  $K_i$ reaches around 2.8 mJ/m<sup>3</sup> at 450°C and is strongly temperature dependent. Using scanning transmission electron microscopy imaging, the interface was found to be smooth and lattice-matched although significant Al diffusion into MgAl<sub>2</sub>O<sub>4</sub> was confirmed. Therefore, the large



**Fig. 1.** *K*<sub>eff</sub> and *K*<sub>i</sub> vs. *T*<sub>ann</sub> of Fe<sub>80</sub>Al<sub>20</sub>/MgAl<sub>2</sub>O<sub>4</sub> stacks.

PMA can be attributed to the creation of effective Fe-O hybridization at the Fe-Al/MgAl<sub>2</sub>O<sub>4</sub> interface through the atomic rearrangement. This work was partly supported by the ImPACT Program of Council for Science, Technology and Innovation, Japan, and JSPS KAKENHI 16H06332 and 16H03852.

**Reference:** [1] H. Sukegawa *et al.*, Appl. Phys. Lett. **110**, 112403 (2017). [2] J.P. Hadorn *et al.*, Acta Mater. **145**, 306 (2018). [3] J.W. Koo *et al.*, Appl. Phys. Lett. **103**, 192401 (2013).